

- Preface p. v
- Acknowledgments p. vii
- Contributors p. xiii
- Introduction
- 1. Silicon Semiconductor Metrology Alain C. Diebold p. 1
- Transistor Fabrication Metrology
- 2. Gate Dielectric Metrology Clive Hayzelden p. 17
- 3. Metrology for Ion Implantation Lawrence A. Larson p. 49
- 4. MOS Device Characterization Eric M. Vogel and Veena Misra p. 59
- 5. Carrier Illumination Characterization of Ultra-Shallow Implants Peter Borden and Laurie Bechtler and Karen Lingel and Regina Nijmeijer p. 97
- 6. Modeling of Statistical Manufacturing Sensitivity and of Process Control and Metrology Requirements for a 0.18- μ m NMOSFET Peter M. Zeitzoff p. 117
- On-Chip Interconnect Metrology
- 7. Overview of Metrology for On-Chip Interconnect Alain C. Diebold p. 143
- 8. Metrology for On-Chip Interconnect Dielectrics Alain C. Diebold and William W. Chism and Thaddeus G. Dziura and Ayman Kanan p. 149
- 9. Thin-Film Metrology Using Impulsive Stimulated Thermal Scattering (ISTS) Michael Gostein and Matthew Banet and Michael A. Joffe and Alex A. Mazney and Robin Sacco and John A. Rogers and Keith A. Nelson p. 167
- 10. Metal Interconnect Process Control Using Picosecond Ultrasonics Alain C. Diebold and Robert Stoner p. 197
- 11. Sheet Resistance Measurements of Interconnect Films Walter H. Johnson p. 215
- 12. Characterization of Low-Dielectric Constant Materials Michael Kiene and Michael Morgen and Jie-Hua Zhao and Chuan Hu and Taiheui Cho and Paul S. Ho p. 245
- 13. High-Resolution Profilometry for CMP and Etch Metrology Anna Mathai and Clive Hayzelden p. 279
- Lithography Metrology
- 14. Critical-Dimension Metrology and the Scanning Electron Microscope Michael T. Postek and Andras E. Vladar p. 295
- 15. Scanned Probe Microscope Dimensional Metrology Herschel M. Marchman and Joseph E. Griffith p. 335
- 16. Electrical CD Metrology and Related Reference Materials Michael W. Cresswell and Richard A. Allen p. 377
- 17. Metrology of Image Placement Alexander Starikov p. 411
- 18. Scatterometry for Semiconductor Metrology Christopher J. Raymond p. 477
- Defect Detection and Characterization
- 19. Unpatterned Wafer Defect Detection Po-Fu Huang and Yuri S. Uritsky and C. R. Brundle p. 515
- 20. Particle and Defect Characterization C. R. Brundle and Yuri S. Uritsky p. 547
- 21. Calibration of Particle Detection Systems John C. Stover p. 583
- Sensor-Based Metrology
- 22. In Situ Metrology Gabriel G. Barna and Bradley Van Eck and Jimmy W. Hosch p. 601
- Data Management

- 23. Metrology Data Management and Information Systems Kenneth W. Tobin, Jr. and Leonard Neiberg p. 679
- Electrical Measurement-Based Statistical Metrology
- 24. Statistical Metrology, with Applications to Interconnect and Yield Modeling Duane S. Boning p. 705
- Overviews of Key Measurement and Calibration Technology
- 25. Physics of Optical Metrology of Silicon-Based Semiconductor Devices Gerald E. Jellison, Jr. p. 723
- 26. Ultraviolet, Vacuum Ultraviolet, and Extreme Ultraviolet Spectroscopic Reflectometry and Ellipsometry J. L. Stehle and P. Boher and C. Defranoux and P. Evrard and J. P. Piel p. 761
- 27. Analysis of Thin-Layer Structures by X-Ray Reflectometry Richard D. Deslattes and Richard J. Matyi p. 789
- 28. Ion Beam Methods Wolf-Hartmut Schulte and Brett Busch and Eric Garfunkel and Torgny Gustafsson p. 811
- 29. Electron Microscopy-Based Measurement of Feature Thickness and Calibration of Reference Materials Alain C. Diebold p. 851
- 30. Status of Lithography Metrology as of the End of 2000 Alain C. Diebold p. 865
- Index p. 869